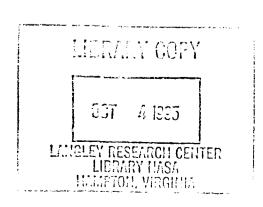
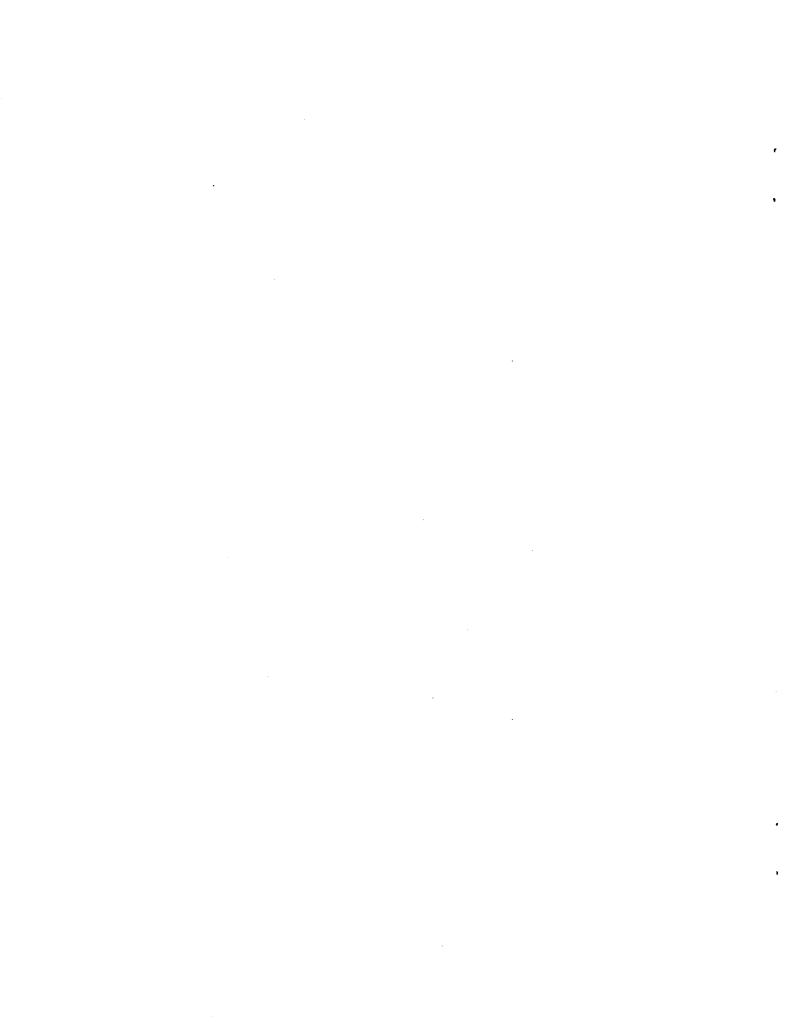
Diamond and Diamondlike Carbon as Wear-Resistant, Self-Lubricating Coatings for Silicon Nitride

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DIAMOND AND DIAMONDLIKE CARBON AS WEAR-RESISTANT, SELF-LUBRICATING COATINGS FOR SILICON NITRIDE

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Recent work on the friction and wear properties of as-deposited fine-grain diamond, polished coarse-grain diamond, and as-deposited diamondlike carbon (DLC) films in humid air at a relative humidity of approximately 40 percent and in dry nitrogen is reviewed. Two types of chemical vapor deposition (CVD) processes are used to deposit diamond films on silicon nitride (Si₃N₄) substrates: microwave-plasma and hot-filament. Ion beams are used to deposit DLC films on Si₃N₄ substrates. The diamond and DLC films in sliding contact with hemispherical bare Si₃N₄ pins have low steady-state coefficients of friction (<0.2) and low wear rates (< 10-7 mm³/N·m), and thus, can be used effectively as wear-resistant, self-lubricating coatings for Si₃N₄ in the aforementioned two environments.

Keywords: Diamond film, DLC film, Tribology, Wear, Friction

1. INTRODUCTION

Structural ceramics such as Si_3N_4 and silicon carbide (SiC) are frequently the materials of choice in engine components, tools, and wear parts, such as turbine rotors, cutting tools, dies, mechanical-face seals, and rolling-element bearings. However, structural ceramics lack inherently good friction and wear properties. Clearly, what is needed is a means to provide acceptable levels of friction and wear properties for structural ceramics. Presently, liquid lubrication or some type of surface modification (e.g., coatings or ion implantation) is employed.

Coefficients of friction for diamond, known to be one of the slipperiest materials, are similar to those of polytetrafluoroethylene in terrestrial environments (1). Natural diamond or high-pressure and high-temperature manufactured diamonds are available as three-dimensional products. However, the CVD diamond films and diamondlike carbon (DLC) films are available in a planar film or sheet and can be grown economically on ceramics such as Si₃N₄. Diamond and DLC films could offer tribologists and designers the combined properties of hard coatings and solid lubrication (2).

In this investigation, fine-grain diamond, coarse-grain diamond, and DLC were deposited on monolithic Si₃N₄ flat substrates. Reciprocating sliding-friction experiments were conducted with smooth flat surfaces of the diamond and DLC films in contact with hemispherical bare monolithic Si₃N₄ pins in humid air and in dry nitrogen. Comparative experiments for friction and wear were also conducted with bare surfaces of monolithic Si₃N₄ flats and a monolithic diamond (110) type IIa flat in contact with bare Si₃N₄ pins. Some earlier data and experimental details on this work and related research are given in references 3 to 9.

2. EXPERIMENT

2.1 Diamond and Diamondlike Carbon (DLC) Films

The as-deposited fine-grain diamond films were produced by a microwave plasma-enhanced CVD technique and are described in detail in references 3 and 4. The polished coarse-grain diamond films were produced by a hot-filament CVD technique and subsequently processed by diamond-wheel polishing. The deposition technique is described in detail in reference 9. The as-deposited DLC films, which are highly dense and pinhole-free, were produced by direct ion beam deposition from a Kaufman ion source (6).

A variety of techniques were used to characterize the diamond and DLC films. Scanning and transmission electron microscopy were used to determine surface morphology and to measure grain sizes. Surface profilometry was used to measure the surface roughness. Raman spectroscopy and Fourier transform infrared spectroscopy were used to characterize diamond quality and structure, while x-ray photoelectron spectroscopy (XPS) was used to characterize surface chemistry. Rutherford backscattering spectroscopy identified any impurities in the films and determined carbon and impurity concentrations. Proton recoil detection measured the hydrogen concentration and x-ray diffraction was used to determine the crystal orientation of the diamond films.

The physical characteristics of the diamond and DLC films are listed in table I. The average surface roughness of the two kinds of diamond and DLC films was small and ranged from 5 to 37 nm root-mean-square. The relatively smooth surface of the as-deposited fine-grain diamond, the polished coarse-grain diamond, and the as-deposited DLC films was attributed to the fine-grain microstructure, the diamond-wheel polishing, and the amorphous phase, respectively.

2.2 Friction and Wear Experiments

Reciprocating sliding friction experiments were conducted with the flats (i.e., diamond and DLC films, monolithic diamond (110) type IIa, and bare monolithic Si₃N₄) in contact with the bare monolithic Si₃N₄ pins in a humid air at a relative humidity of approximately 40 percent and in dry nitrogen. Details of the friction apparatus, the experimental procedures, and the wear measurements are described in reference 4; the experimental conditions are listed in table II. Hot-pressed, polycrystalline, magnesia-doped silicon nitride (92 Si₃N₄-4MgO-4Y₂O₃) was used as the flat and pin materials in the sliding friction experiments and as the substrate material for diamond and DLC films.

3. FRICTION AND WEAR PROPERTIES

Figure 1 presents coefficients of friction in humid air and dry nitrogen for the as-deposited fine-grain diamond film, the as-deposited DLC film, and the bare Si_3N_4 flat in sliding contact with the bare Si_3N_4 pins. The friction data indicate that the steady-state coefficient of friction was considerably lower for the as-deposited fine-grain diamond and as-deposited DLC films than for bare Si_3N_4 flat in humid air and dry nitrogen. Using a smooth diamond and DLC film with a Si_3N_4 substrate reduces the steady-state coefficient of friction to an acceptable level (e.g., <0.2) in humid air and dry nitrogen. Note that the frictional results on the as-deposited fine-grain diamond and DLC films couple are consistent with those on the natural monolithic diamond (111) in humid air and dry nitrogen (5).

Generally, for the diamond film, the coefficient of friction decreased with an increase in the number of passes regardless of environment, reaching an equilibrium value after a certain number of passes. The high initial coefficients of friction observed for the as-deposited fine-grain diamond film in humid air and dry nitrogen predominantly resulted from the plowing or microcutting actions of some sharp edges of asperities present on the as-deposited fine-grain diamond film surface. As the sliding continued and the pin passed repeatedly over the same track, the tips of the sharp edges of asperities on the track quickly became dull and the coefficient of friction was appreciably affected by blunting the edges of asperities. Therefore, the coefficient of friction is markedly reduced in the initial stage of the experiment.

For the DLC film, the coefficient of friction was almost constant in a humid-air environment, but decreased with the increasing number of passes in dry nitrogen, reaching an equilibrium value. For the bare Si_3N_4 flat, the coefficient of friction increased with an increase in number of passes regardless of environment, reaching an equilibrium value after a certain number of passes. For the bare Si_3N_4 flat, the low initial coefficients of friction observed in humid air and dry nitrogen predominantly resulted from a contaminant layer formed on Si_3N_4 surfaces by the interaction of the surface with the environment.

Thin contaminant layers are unavoidably present on every surface of any solid that has been exposed to air or nitrogen. The layers are made up of contaminants such as adsorbed gases, water vapor, and hydrocarbons and have a thickness of atomic dimensions (around 2-nm thick). These contaminants can greatly reduce friction and accordingly provide lubrication as seen in the initial stage of the experiment. Under the repeated sliding, the contaminant surface layers are removed, thus, direct contact of the fresh surfaces is unavoidable. This situation applies to the sliding contact in the condition of steady-state (equilibrium) coefficient of friction for the Si₃N₄-Si₃N₄ couples (fig. 1b).

It is well known that sliding action in humid air increases the chemical reaction rate between Si₃N₄ and water vapor. Many researchers have found that the tribochemical interactions produce reaction products (i.e., silicon dioxide) and lead to a decrease in the coefficient of friction for the Si₃N₄-Si₃N₄ couple (e.g., 10). The frictional results for the bare Si₃N₄ flat shown in figure 1 are consistent with many researchers' findings. However, for the diamond and DLC films, the formation of silicon dioxide on the counterfacing Si₃N₄ pin in humid air leads to increases in the coefficient of friction. The presence of the silicon oxide layer on the bare Si₃N₄pin plays a role in the relatively high friction process for the diamond and DLC films.

Figure 2 presents steady-state (equilibrium) coefficients of friction and wear rates in humid air and dry nitrogen for the as-deposited fine-grain diamond, polished coarse-grain diamond, and as-deposited DLC films, bare monolithic diamond (110) type IIa flat, and bare monolithic Si_3N_4 flat in contact with bare Si_3N_4 pins. The friction and wear data indicate conditions that reduce friction (e.g., a particular combination of environment and material) usually reduce wear rate as well.

The results presented in figure 2 demonstrate that the as-deposited fine-grain diamond, polished coarse-grain diamond, and DLC films improved both friction and wear properties of Si_3N_4 . The steady-state coefficients of friction and the wear rates of the bare Si_3N_4 flat are high in humid air and dry nitrogen. On the other hand, all the as-deposited fine-grain diamond, polished coarse-grain diamond, DLC, and diamond (110) type IIa flat in contact with bare Si_3N_4 pins have a low steady-state coefficient of friction (<0.2) and a low wear rate (10-7 mm³/N·m or less). Those carbon films can be effective wear-resistant, self-lubricating films for ceramics.

4. CONCLUDING REMARKS

As-deposited fine-grain diamond, polished coarse-grain diamond, and as-deposited DLC films can be effectively used as wear-resistant, self-lubricating coatings for silicon nitride (Si₃N₄) in humid air and dry nitrogen. Those films (deposited on Si₃N₄ substrates) in sliding contact with bare Si₃N₄ pins in humid air at a relative humidity of 40 percent and in dry nitrogen have low steady-state coefficients of friction (< 0.2) and low wear rates (< 10-7 mm³/N·m).

5. ACKNOWLEDGMENTS

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TABLE I.—COMPARISON OF AS-DEPOSITED FINE-GRAIN DIAMOND, POLISHED COARSE-GRAIN DIAMOND, AND AS-DEPOSITED DIAMONDLIKE CARBON (DLC) FILMS

Condition	As-deposited fine-grain diamond film	Polished coarse-grain diamond film	As-deposited DLC film	
Composition	Essentially carbon, < 2.5 at % hydrogen	Essentially carbon	70 at % carbon and 30 at % hydrogen	
Microstructure	Polycrystalline	Polycrystalline	Amorphous	
Crystal orientation	<110>	<111>		
Grain size, nm	20 to 100	10 000	***************************************	
Raman spectrum	Sharp peak centered near 1330 cm ⁻¹ ; broad humps centered near 1320 cm ⁻¹ and in 1500 to 1530 cm ⁻¹ range	Sharp peak centered near 1330 cm ⁻¹ ; broad humps centered near 1320 cm ⁻¹ and in 1500 to 1530 cm ⁻¹ range	Broad peak at 1539 cm ⁻¹ ; weak shoulder peak around 1340 cm ⁻¹	
Atom-bonding state	sp ³ and sp ² (variable ratio, very roughly 1:1)	sp ³ and sp ² (variable ratio)	sp ³ and sp ²	
Surface morphology	Granulated or spherulitic: spherical asperities of different sizes	Flat, polished	Pinhole-free uniform smooth surface	
Surface roughness, rms, nm	6 to 37	6 to 25	5	
X-ray photoelectron spectroscopy (XPS) spectrum	Carbon and oxygen peaks	Carbon and oxygen	Carbon and oxygen	
C/O ratios in XPS spectrum	os in XPS spectrum 8 to 12			

TABLE II.—CONDITIONS OF SLIDING FRICTION EXPERIMENTS IN HUMID AIR AND DRY NITROGEN

[Pin specimens were polished with 3-µm diamond powder and 1-µm aluminum oxide powder, respectively. Hemispherical pin specimen radius, 1.6 mm.]

Contact	Hemispherical pin on flat configuration
Load, N	
Environment	
	and dry nitrogen (relative humidity
	less than 1 percent)
Temperature, *C	23
Motion	Unidirectional sliding
	86
	30 000

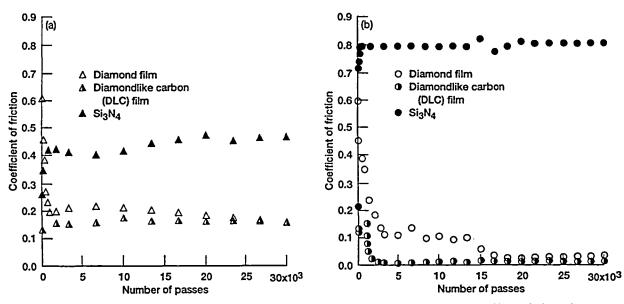


Figure 1.—Coefficients of friction for as-deposited fine-grain diamond film, as-deposited DLC film, and bare Si₃N₄ flat in contact with Si₃N₄ pins as function of number of passes. (a) Humid air. (b) Dry nitrogen.

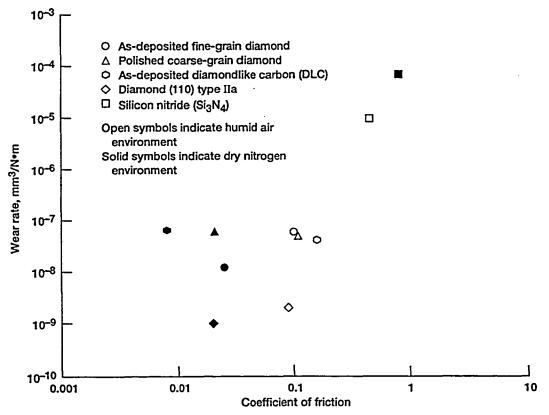


Figure 2.—Coefficients of friction and wear rates of as-deposited fine-grain diamond, polished coarse-grain diamond, as-deposited DLÇ, diamond (110) type IIa, and Si₃N₄ in contact with Si₃N₄ in humid air and dry nitrogen.



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